



## Materials Processing for Production of Nanostructured Thin Films

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### Message from the Guest Editor

The production of thin films presenting features on the scale of nanometers is important in different areas of technology, including array technology; displays; surfaces with special optical properties; surfaces with novel wetting or adhesion behavior; as surfaces for cell growth, catalysis, solar energy, chemical or biological sensing; and in medical devices. Such thin films can have unique electronic, optical, magnetic, chemical, biomaterial, or interfacial properties. The processes by which such thin films are produced have expanded to include novel approaches using chemical vapor deposition, physical vapor deposition, atomic layer deposition, patterning using laser or ion beams, self-organized polymerization reactions, controlled corrosion, electrodeposition onto templates, chemical surface modification, electroless deposition, and other specialized material processing methods. This Special Issue is intended to feature methods for producing nanostructured thin films, new developments, detailed characterizations of thin film structure and properties, and examples of their application.





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